

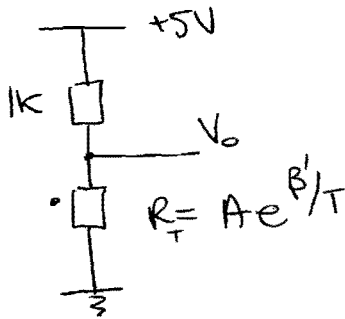
ENGINEERING TRIPOS PART IIB 2012
4B13 - ELECTRONIC SENSORS AND INSTRUMENTATION

CRIB

4B13 2012

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1 (a)



$$V_0 = \frac{R_T \cdot 5V}{(1000 + R_T)}$$

$$R_T = 1000 @ T = 293K$$

$$\beta' = 3300$$

$$\therefore \ln 1000 = \ln A + \frac{3300}{293}$$

$$6.91 = \ln A + 11.26$$

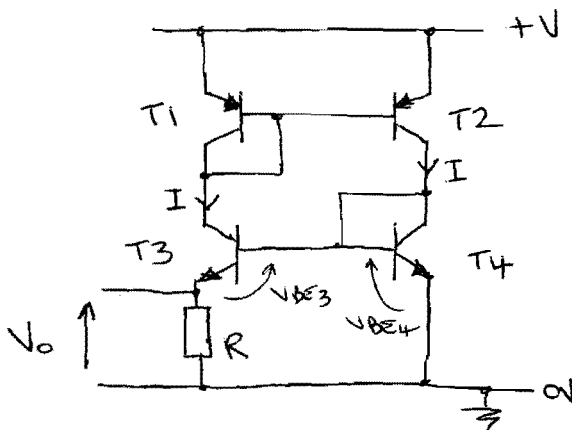
$$\therefore A = 0.0129$$

$$s_{20}, \text{ at } 55^\circ\text{C} = 328K, R_T = 0.0129 e^{\frac{3300}{328}} = 302 \Omega$$

$$\therefore V_0 = \frac{302 \times 5}{1302} = 1.16V$$

[20%]

(b)



Ebers-Moll eqn. for bipolar transistors.

$$I_c = I_s e^{V_{BE}/(kT/q)}$$

with $V_e = kT/q$

T1 and T2 are matched and connected as current mirrors to T3 and T4. T3 is scaled to have an area of $r \times$ that of T4 - so the current density is $\div r$ for T3.

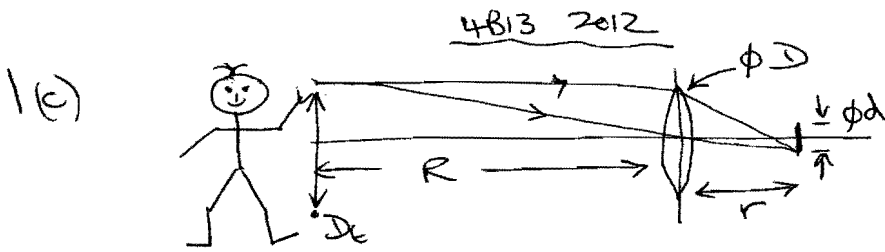
Ebers-Moll for current density:

$$J_{c3} = J_{s3} e^{V_{BE3}/V_e} \quad \text{and} \quad J_{c4} = J_{s4} e^{V_{BE4}/V_e}$$

now $r J_{c3} = J_{c4}$ and $J_{s3} = J_{s4} = J_s$ as this is a material property

$$\text{so } r J_s e^{V_{BE3}/V_e} = J_s e^{V_{BE4}/V_e} \Rightarrow V_e \ln r = V_{BE4} - V_{BE3} = V_0$$

$$\therefore V_0 = \frac{kT}{q} \ln r = \text{const.} \times T \quad \text{typ. range } -50^\circ\text{C} - 150^\circ\text{C}$$



$$D = 30 \text{ mm}$$

$$r = 25 \text{ mm}$$

$$d = 5 \text{ mm}$$

Lambert's Law: $S_W = \frac{W \cos \theta}{\pi} A S_w = \text{power emitted in solid angle } S_w$

with $W = \text{total power emitted per unit area}$
 $\theta = \text{angle to surface normal}$
 $A = \text{area of emitting surface}$

Stephan's Law: $W = \epsilon \sigma_{SB} T^4 = \text{power emitted per unit area}$

$\epsilon = \text{emissivity} = 0.90$

$T = \text{absolute temperature}$

$\sigma_{SB} = \text{Stephan-Boltzmann constant} = 5.6 \times 10^{-8} \text{ W m}^{-2} \text{ K}^{-4}$

$$\Rightarrow S_W = \frac{\epsilon \sigma_{SB} T^4}{\pi} \cdot \frac{\pi D^2}{4} \cdot \frac{\pi D^2}{4} \cdot \frac{4\pi}{4\pi R^2} = \frac{\epsilon \sigma_{SB} T^4 \pi d^2 D^2}{16 r^2}$$

(since $Dt/R = d/r$ by similar Δ 's.) $\Rightarrow S_W = \underline{3.2 \text{ mW}}$

[30%]

(d) Metal strain gauge has G.F. = 2

Power dissipation in sg. = $0.01^2 \times 120 = 12 \text{ mW} = P$

with 0.1 mm Hitec adhesive and area of 5 mm^2

$$P = \frac{k A \Delta T}{\epsilon} = \frac{0.25 \times 5 \times 10^{-6}}{0.1 \times 10^{-3}} \Delta T = 0.012$$

$$\therefore \Delta T = 0.96 \text{ }^\circ\text{C} \Rightarrow 0.096\% \text{ change in resistance}$$

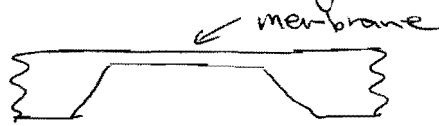
with a G.F. of 2, this is equivalent to strain of 0.048%.

(which is quite a lot compared to strain max of eg: 0.5%).

[30%]

2 (a)

Pressure sensor usually bulk micromachined from Si wafer



- membrane / diaphragm is fabricated with Boron doping and anisotropic etching with hot KOH soln. - the doped section of Si forms the thin section

For surface and bulk micromachining the processes involved are • photolithography:

spin-on resist, expose, develop, etch, remove

- sacrificial layers, etch masks + etch steps
- deposition of layers for surface structures
poly-Si, SiO₂, Si₃N₄, metals
- etching RIE dry anisotropic, directional
KOH wet anisotropic + isotropic for non-crystalline mats.
- bonding wafer sections

- fabrication of integrated electronics + strain gauge sensors by IC process steps (CMOS).

- readout methods: piezo-resistive using deposited or doped strain gauges in stress areas + reference devices for temperature compensation

: capacitive using electrodes with variable air gaps to monitor displacements

piezo-resistive

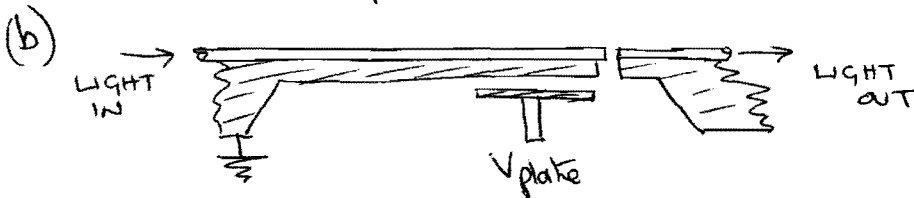
capacitive

- | | |
|--------------------------------------|--------------------------------|
| + low impedance, robust signal | - high imp., local electronics |
| - higher power consumption | + low power consumption |
| - thermal drift | + low temperature coeff. |
| - not so well suited to surface MEMS | + good for surface MEMS |

2(a) contd

Accelerometers - usually planar devices made with surface micromachining with capacitive readout technique. Proof mass and inter-digital capacitor fingers and suspension beams are patterned and sacrificial layer etched away to leave a suspended structure.

Pressure sensor - uses a membrane left from bulk etching - readout can be via strain gauges diffused & patterned into the diaphragm. [40%]



(i) $C = \frac{A\epsilon_0}{d} = \frac{(15 \times 10^{-6})^2 \cdot 8.854 \times 10^{-12}}{5 \times 10^{-6}} \approx 3.98 \times 10^{-16} \text{ F}$

(ii) In order to deflect the beam by $2 \mu\text{m}$, the capacitor force $F \Rightarrow \delta = \frac{FL^3}{3EI} = 2 \times 10^{-6}$ with $L = 10^{-3} \text{ m}$
 $E = 145 \text{ GN m}^{-2}$

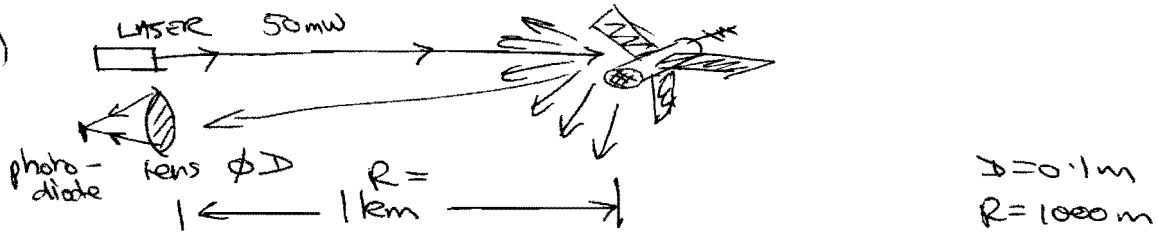
$I = \frac{1}{12} bd^3$ with $b = 15 \times 10^{-6} \text{ m}$
 $d = 5 \times 10^{-6} \text{ m}$ } $I = 1.56 \times 10^{-22} \text{ m}^4$ (data book 140-155)

$\therefore F = 1.36 \times 10^{-7} \text{ N} = \frac{1}{2} V_p^2 \frac{\partial C}{\partial x}$ with $C = \frac{A\epsilon_0}{x}$, $\frac{\partial C}{\partial x} = -\frac{C}{x}$

$\therefore F = \frac{1}{2} V_p^2 \frac{C}{d} = \frac{1}{2} V_p^2 \frac{3.98 \times 10^{-16}}{5 \times 10^{-6}}$ $\therefore V_p = 58.5 \text{ V}$ [40%]

(c) m, Beam mass = $\rho_{\text{Si}} \times L \times b \times d = 1.74 \times 10^{-13} \text{ kg}$, $\rho_{\text{Si}} = 2.32 \text{ kg m}^{-3}$
 Guessimate centre of vibrating mass as $2/3$ along beam = 0.66 mm , then
 spring constant, s , = $F/\delta = \frac{3EI}{L^3} = 0.236 \text{ N m}^{-1}$ and $f_{\text{res}} = \frac{1}{2\pi} \sqrt{\frac{s}{m}}$
 $\therefore f_{\text{res}} = 185 \text{ kHz}$ so $f_{\text{amb}} = \frac{Q}{\pi} = \frac{50}{\pi} = 0.27 \text{ ms}$ [20%]

3(a)



$$\text{Collected light} = \frac{\frac{\pi D^2}{4} \cdot 500 \times 10^{-3}}{2\pi R^2} = 625 \text{ pW}$$

@ 0.36 A/W, the photo-current = 225 pA [25%]

(b) with amplitude modulation at 120 MHz, the wavelength of the modulation = $\frac{3 \times 10^8}{120 \times 10^6} = 2.5 \text{ m}$

for a path length change of $2 \times 50 \text{ m}$, we get 40 beats at the mixer $\therefore 50 \text{ m/s} \Rightarrow$ 40 Hz Doppler. [15%]

(c) for a closing speed of 500 m/s, the required bandwidth is 400 Hz. Hence noise sources are:-

Amp. current noise: $0.06 \times 10^{-12} \times \sqrt{400} \times 10^4 = 1.2 \times 10^{-8} \text{ V}_{\text{rms}}$
 $i_{\text{noise}} \times R$

Amp voltage noise: $1.5 \times 10^{-9} \times \sqrt{400} = 3.0 \times 10^{-8} \text{ V}_{\text{rms}}$

Resistor thermal noise: $\sqrt{4kTRB} = (4 \cdot 1.38 \times 10^{-23} \cdot 300 \cdot 10^4 \cdot 400)^{1/2} = 25.7 \times 10^{-8} \text{ V}_{\text{rms}}$

$\therefore V_{\text{noise}} = \sqrt{\sum V_n^2} = 259 \text{ nV}_{\text{rms}}$

$V_{\text{sig}} = 225 \times 10^{-12} \text{ A} \times 10^4 \Omega = 2.25 \mu\text{V}$

\therefore S/N ratio ≈ 8.7 (ok but not very good!) [35%]

3 (d) Photon energy at 635 nm given by $E = \frac{hc}{\lambda}$
 $\therefore E = \frac{6.626 \times 10^{-34} \cdot 3 \times 10^8}{635 \times 10^{-9}} = 3.13 \times 10^{-19} \text{ J}$

\therefore 1W of optical power = $\frac{1}{3.13 \times 10^{-19}}$ photons/sec

So, for a Q.E. of unity, the current would be $\frac{1.6 \times 10^{-19}}{3.13 \times 10^{-19}} = 0.51 \text{ A/W}$

Hence for 0.36 A/W the Q.E. = 0.71 at this wavelength

[10%]

(e) To measure range, the flight time of the laser beam must be determined. This can be done by pulsing the laser and measuring the delay for the reflected beam to return or the laser can be continuously modulated at a pair of frequencies and the phase shift determined for each — this allows the range ambiguity to be resolved for repeated wavelengths of a single modulation frequency.

For 1000m range, the max. pulse repeat rate = $\frac{3 \times 10^8}{2000} = 150 \text{ kHz}$ before there is pulse-echo overlap.

for twin frequency modulation, the range ambiguity appears

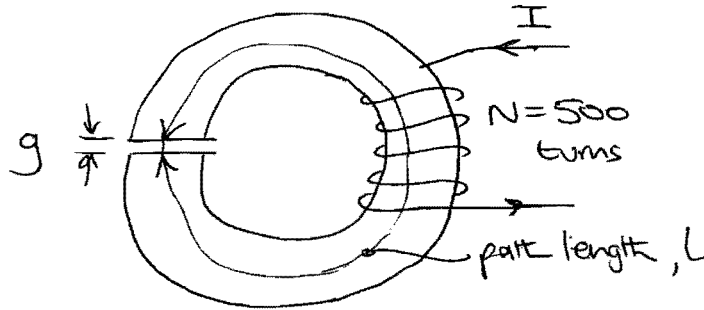
when $n \lambda_1 = (n+1) \lambda_2 = 2000 \text{ m}$

with $\lambda_1 = \frac{3 \times 10^8}{120 \times 10^6} = 25 \text{ m}$ then $n = 80$, so $\lambda_2 = 24.69 \text{ m}$

so for λ_2 , $f_2 = 121.5 \text{ MHz}$

[15%]

4(a)



$g = 1 \text{ mm or } 0.5 \text{ mm}$
 $L = 105\pi \text{ mm}$
 $A = 100 \text{ mm}^2$

Under zero load $g = 1 \text{ mm}$ $\int H \cdot dl = \oint J \cdot ds$

$NI = H_m L + H_0 g$ and $B_m = B_0 = B$ for flux conservation
 with $B_m = \mu_0 \mu_r H_m$, $B_0 = \mu_0 H_0$

$NI = H_0 (g + L/\mu_r) \Rightarrow B = \frac{\mu_0 NI}{(g + L/\mu_r)}$ and $\phi = BA$

$L = \frac{N\phi}{I} = \frac{\mu_0 N^2 A}{(g + L/\mu_r)}$

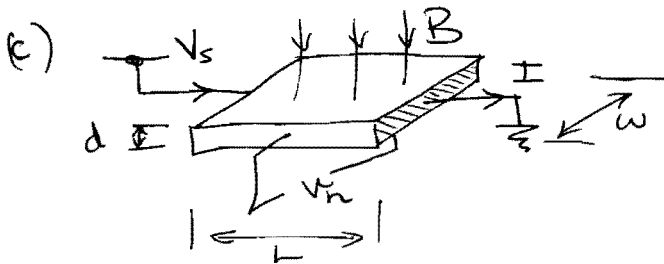
so with $N = 500$, $A = 100 \times 10^{-6} \text{ m}^2$
 $g = 10^{-3} \text{ m}$, $L = 0.33 \text{ m}$
 $\mu_r = 1500$, $\mu_0 = 4\pi \times 10^{-7} \text{ Hm}^{-1}$

$L_{\text{zero load}} = 0.0257 \text{ H}$ (1mm gap)

$L_{500N} = 0.0435 \text{ H}$ (0.5mm gap)

[25%]

(b) $B_{ON} = \frac{\mu_0 NI}{1.22 \times 10^{-3}} = 0.515 \text{ T}$, $B_{500N} = 0.873 \text{ T}$



$Bqva = \frac{qva}{w}$ for force bal.

$va = \frac{\mu Vs}{L}$

$\therefore \frac{B\mu Vs w}{L} = v_n = 0.75B$

So, @ zero load, $v_n = 0.386 \text{ V}$
 @ 500N, $v_n = 0.655 \text{ V}$

$\Delta V = 0.269 \text{ V}$

[35%]

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$$5(a) \quad V = N \frac{d\phi}{dt} = 2\pi f N A B$$

$$\text{So for } f = 40 \text{ kHz}, B = 10^{-3} \text{ T}, N = 200, A = \frac{\pi}{4} (4 \times 10^{-2})^2$$

$$\therefore V = 63 \text{ V amplitude.} = \underline{44.6 \text{ V}_{\text{rms}}} \quad [15\%]$$

$$(b) \quad \text{Acoustic impedance of air} = \rho v = 408 \text{ kg m}^{-2} \text{ s}^{-1}$$

$$\text{Transducer acoustic impedance} = 10^5 \text{ kg m}^{-2} \text{ s}^{-1}$$

$$\therefore \text{Coupling coeff} = \frac{4 Z_t Z_a}{(Z_t + Z_a)^2} = 0.0162$$

$$\text{Power in transducer} = \frac{V^2}{R} = \frac{44.6^2}{5000} = 0.4 \text{ W}$$

$$\text{Power converted to ultrasound} = 0.4 \times 0.15 = 0.06 \text{ W}$$

$$\text{Ultrasound coupled to air} = 0.06 \times 0.0162 = 0.96 \text{ mW}$$

At a range of 2m, with isotropic radiator (no atten.)

$$\text{ultrasonic power density} = \frac{9.6 \times 10^{-4}}{4\pi 2^2} = 1.91 \times 10^{-5} \text{ W m}^{-2}$$

$$\text{With attenuation of } 2 \text{ dB m}^{-1} \times 2 \text{ m} = -4 \text{ dB} = \times 10^{-4/10}$$

$$P_{\text{uls}} \Rightarrow \underline{7.64 \times 10^{-5} \text{ W m}^{-2}} = \times 0.4$$

[35%]

$$(c) \quad \text{Power intercepted by receiving transducer} = \frac{\pi d^2}{4} \times P_{\text{uls}} \\ = \frac{\pi}{4} (4 \times 10^{-2})^2 \times 7.64 \times 10^{-5} = 9.60 \times 10^{-9} \text{ W}$$

$$\text{of this, the power coupled into the transducer} = \times 0.0162$$

$$= 1.55 \times 10^{-10} \text{ W}$$

$$\text{of this, the power converted to electrical signal} = \times 0.15$$

$$= 2.33 \times 10^{-11} \text{ W}$$

5(c) contd.

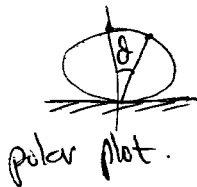
Thus the power delivered to a 50Ω matched load

$$= 2.33 \times 10^{-11} = \frac{V_r^2}{R} \quad \therefore V_r = 0.34 \text{ mV into load}$$

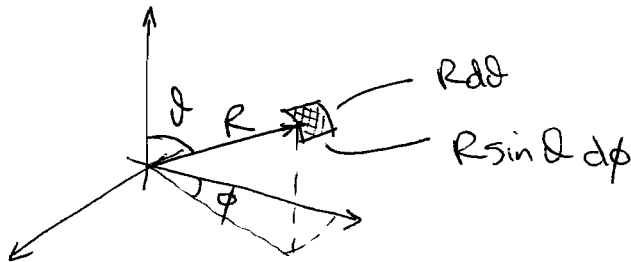
Hence, open circuit voltage = $0.68 \text{ mV rms} \approx 2 \text{ mV pp}$

[30%]

(d) A Lambertian beam profile has a $\cos\theta$ dependence on emitted intensity, where θ is the angle to the normal.



$$I = I_0 \cos\theta$$



$$\text{Total power emitted, } P = \int_0^{\pi/2} \int_0^{2\pi} I_0 \cos\theta R^2 \sin\theta d\phi d\theta$$

$$\therefore P = I_0 R^2 2\pi \int_0^{\pi/2} \underbrace{\sin\theta \cos\theta d\theta}_{= 1/2 \sin 2\theta}$$

$$\therefore P = I_0 R^2 2\pi \left[-1/2 \cos 2\theta / 2 \right]_0^{\pi/2} = I_0 R^2 \pi$$

$$\therefore I_0 = \frac{P}{\pi R^2} \quad \text{compared to } \frac{P}{4\pi R^2} \text{ isotropic (full sphere)}$$

Hence received signal power will be 16x greater (gain both ways) = x4 for signal voltage. But, the system is now directional, so this is only achieved for optimal alignments. In some cases the signal could be worse.

[20%]

4B13 comments

Q1 Temperature & strain sensing

Quite a popular question which was well answered by most candidates. Most knew how to calculate the thermistor resistance correctly although there were a number of errors in the transistor circuit. The pyrometer and strain gauge sections were mainly correctly answered.

Q2 MEMS optical switch

A rather unpopular question only attempted by about 10% of the candidates. The MEMs process description generally lacked detail, although all who attempted the question knew the structure of accelerometers and pressure sensors. The second half of the question on the cantilever beam was quite well answered, but the settling time was poorly estimated in many cases.

Q3 Optical velocity / range sensing

A popular and well attempted question, which was well answered. The signal magnitude and Doppler frequency were correctly estimated in most cases and the noise calculation was quite well done – some chose to use a wider bandwidth than the Doppler frequency; this was equally valid. The quantum efficiency of the photodiode was also correctly determined by most people.

Q4 Electromagnetic load cell

Another fairly popular question with a good range of answers. Most could evaluate the sensor inductance correctly although there were minor errors concerning the toroid cross-sectional area. The Hall sensor section was also well answered but only a few candidates correctly ascertained the magnetic force offset in the last part.

Q5 Inductive / ultrasonic detection system

This was the most popular question, being answered by almost all candidates. The induced voltage in the coil was simple, but stumped a few candidates. The ultrasonic calculations were generally well done although a number assumed 'isotropic' to mean only a hemisphere. The final part on a Lambertian beam profile was correctly interpreted by most candidates, but they tended to get the details wrong.